Erratum: Structure and electrical conductivity of polycrystalline silicon films grown by molecular-beam deposition accompanied by low-energy ion bombardment of the growth surface [Semiconductors 31, 237–240 (March 1997)]

D. A. Pavlov, A. F. Khokhlov, D. V. Shungurov, and V. G. Shengurov

Fiz. Tekh. Poluprovodn. **31** (October 1997)

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The spelling of the name of the third author of this article should read as follows: D. V. Shengurov.